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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/724,402	12/01/2003	Klaus Simon	081468-0307087	8896
909	7590 04/27/2006	EXAMINER		
	Y WINTHROP SHAW	KIM, PETER B		
	P.O. BOX 10500 MCLEAN, VA 22102		ART UNIT	PAPER NUMBER
			2851	
			DATE MAILED: 04/27/2006	

Please find below and/or attached an Office communication concerning this application or proceeding.

			H			
Office Action Summary		Application No.	Applicant(s)			
		10/724,402	SIMON ET AL.			
		Examiner	Art Unit			
		Peter B. Kim	2851			
Period fo	The MAILING DATE of this communication apor Reply	pears on the cover sheet with t	the correspondence address			
WHIC - Exte after - If NC - Failu Any	IORTENED STATUTORY PERIOD FOR REPLICATION OF THE MAILING INTERIOR OF THE MAILI	DATE OF THIS COMMUNICA- .136(a). In no event, however, may a reply d will apply and will expire SIX (6) MONTHS te, cause the application to become ABAND	TION.  be timely filed  from the mailing date of this communication.  DONED (35 U.S.C. § 133).			
Status						
1)⊠	Responsive to communication(s) filed on 03 M	March 2006.				
2a) <u></u>	This action is <b>FINAL</b> . 2b)⊠ Thi	2b)⊠ This action is non-final.				
3)[	☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
	closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.					
Disposit	ion of Claims	·				
4)⊠	Claim(s) 1-16 is/are pending in the application	n.				
	4a) Of the above claim(s) is/are withdrawn from consideration.					
5)[	5) Claim(s) is/are allowed.					
6)⊠	Claim(s) <u>1-16</u> is/are rejected.					
7)	Claim(s) is/are objected to.					
8)	Claim(s) are subject to restriction and/o	or election requirement.				
Applicat	ion Papers	•				
9)[	The specification is objected to by the Examin	er.				
	The drawing(s) filed on <u>03 March 2006</u> is/are:		ed to by the Examiner.			
	Applicant may not request that any objection to the					
	Replacement drawing sheet(s) including the correct	ction is required if the drawing(s) i	s objected to. See 37 CFR 1.121(d).			
11)	The oath or declaration is objected to by the E	examiner. Note the attached O	ffice Action or form PTO-152.			
Priority (	under 35 U.S.C. § 119		•			
• • •	Acknowledgment is made of a claim for foreign ⊠ All b) Some * c) None of:	n priority under 35 U.S.C. § 11	9(a)-(d) or (f).			
	1. Certified copies of the priority documents have been received.					
	2. Certified copies of the priority documents have been received in Application No					
	3. Copies of the certified copies of the price	-	eived in this National Stage			
	application from the International Burea	` ' ' '	•			
* \$	See the attached detailed Office action for a list	t of the certified copies not rec	eived.			
Attachmen	• •	A T 1 - 4	(DTO 412)			
	ce of References Cited (PTO-892) ce of Draftsperson's Patent Drawing Review (PTO-948)		mary (PTO-413) ail Date			
3) 🛛 Infor	mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08 or No(s)/Mail Date 32006.	5) Notice of Inform 6) Other:	mal Patent Application (PTO-152)			

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#### **DETAILED ACTION**

Applicant's arguments filed on March 3, 2006 have been fully considered.

# Claim Rejections - 35 USC § 112

The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claims 1-13, and 16 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

Regarding claims 1, 11, and 16, the terms "exposure" and "exposing" are not clear. In claim 1, the substrate is subjected to "different fluid or exposure processes." Does the term "exposure" refer to projecting the patterned beam and exposing the substrate to the beam or does it mean exposing it to the fluid? Since claims 11 and 16 claim exposing the substrate to a fluid, do fluid process and exposure process mean the same thing?

Further regarding claim 1, the term "different" is not clear. Is the substrate subject to different types of fluids? Are the fluid process and the exposure process the same? If the processes are not the same, is the term "different" redundant?

Regarding claims 1, 11 and 16, do substrate and fluid interact and cause a process to take place without being exposed to the projection beam? If yes, what does that process establish as opposed to exposure to the projection beam?

The remaining claims, not specifically mentioned, are rejected for incorporating the defects from the base claim by dependency.

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# Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 11 and 16 are rejected under 35 U.S.C. 102(b) as being anticipated by Garner et al. (Garner) (2002/0041420).

Garner discloses a lithographic projection apparatus and a device manufacturing method comprising a radiation system (12), a patterning structure (34) configured to pattern the projection beam; a substrate table configured to hold a substrate (24), a projection system (22) and a fluid processing cell in communication with a surface of a substrate (36, 48), and different areas of the substrate subject to different fluid or exposure process simultaneously (Fig. 3).

Garner discloses a plate member (64) having walls and contacting the substrate. Garner discloses fluid inlet and outlet (Fig. 3, ref. 50, 52).

## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-16 are rejected under 35 U.S.C. 103(a) as being unpatentable over Garner in view of Amorese et al. (Amorese) (2004/0043494).

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Garner discloses a lithographic projection apparatus and a device manufacturing method comprising a radiation system (12), a patterning structure (34) configured to pattern the projection beam; a substrate table configured to hold a substrate (24), a projection system (22) and a fluid processing cell in communication with a surface of a substrate (36, 48), and different areas of the substrate subject to different fluid or exposure process simultaneously (Fig. 3).

Garner discloses a plate member (64) having walls and contacting the substrate. Garner discloses fluid inlet and outlet (Fig. 3, ref. 50, 52). However, Garner does not disclose the fluid processing cell comprising a plurality of separate chambers. Amorese discloses in Fig. 1 and para 0062-0068 and 0090, having separate chambers for the fluid. Therefore, it would have been obvious to one of ordinary skill in the art at the time of the invention to provide the separate walls for the fluid to the invention of Garner in order to prevent unintended chemical reaction as taught by Amorese in para 0021 and 0090.

## Response to Arguments

Regarding the list of patent applications submitted, the list are considered but not initialed and returned because application numbers are not printed on the face of the patent.

Regarding claim 11 and 16, because the fluid is provided to the substrate and only a portion (the target portion) of the substrate is exposed to the patterned beam, fluid processing and exposure are carried out at least partially simultaneously.

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#### Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Peter B. Kim whose telephone number is (571) 272-2120. The examiner can normally be reached on 8:00 AM - 5:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Judy Nguyen can be reached on (571) 272-2258. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Peter B. Kim
Primary Examiner
Art Unit 2851

April 12, 2006